

F/G. 2

THERMAL ANNEAL

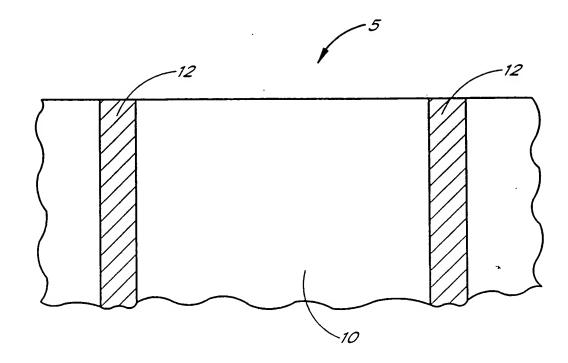
PLASMA TREATMENT

HYDROXIDE

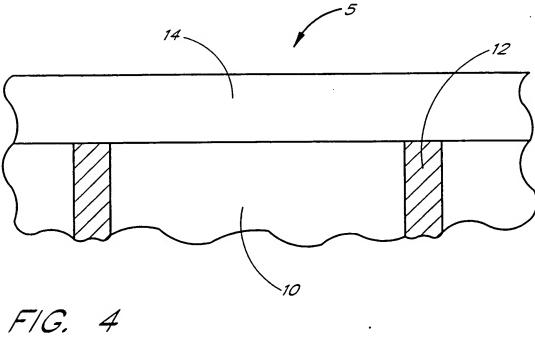
ORGANOSILANE TO REACTION CHAMBER

INTRODUCE

FORM SILICON



F/G. 3



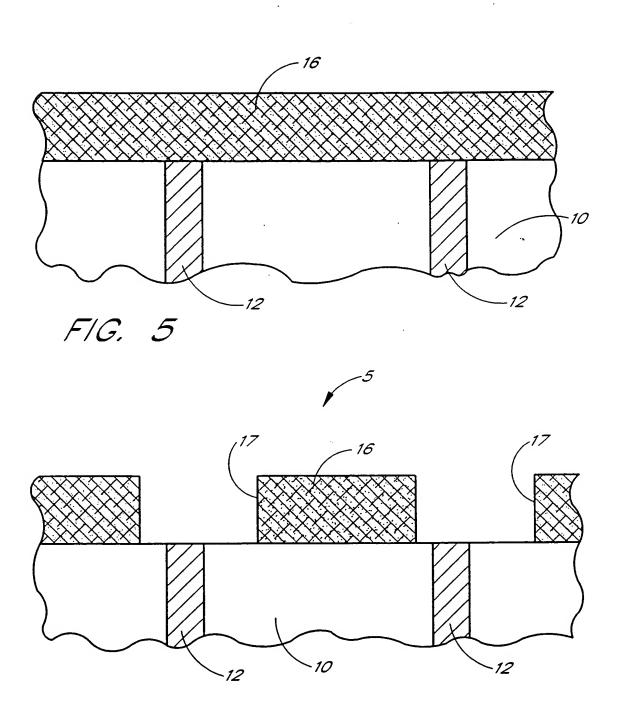
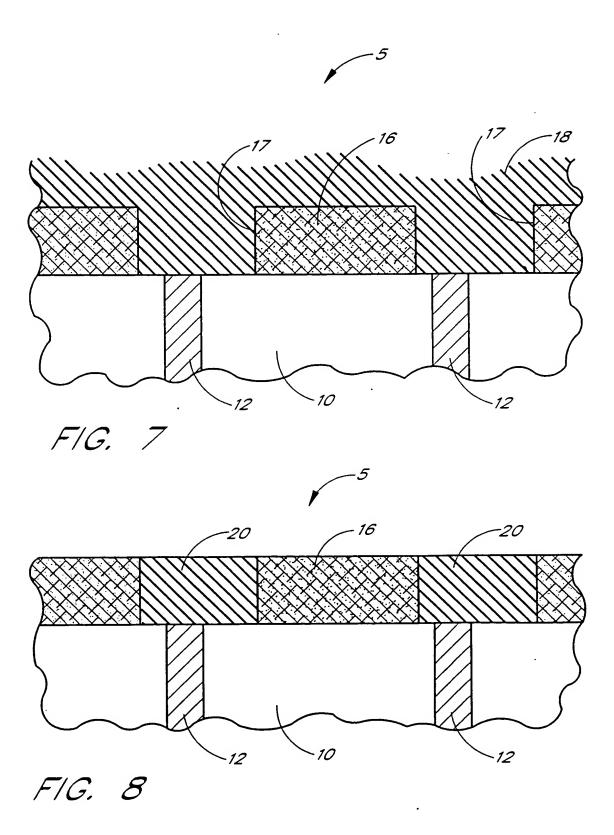
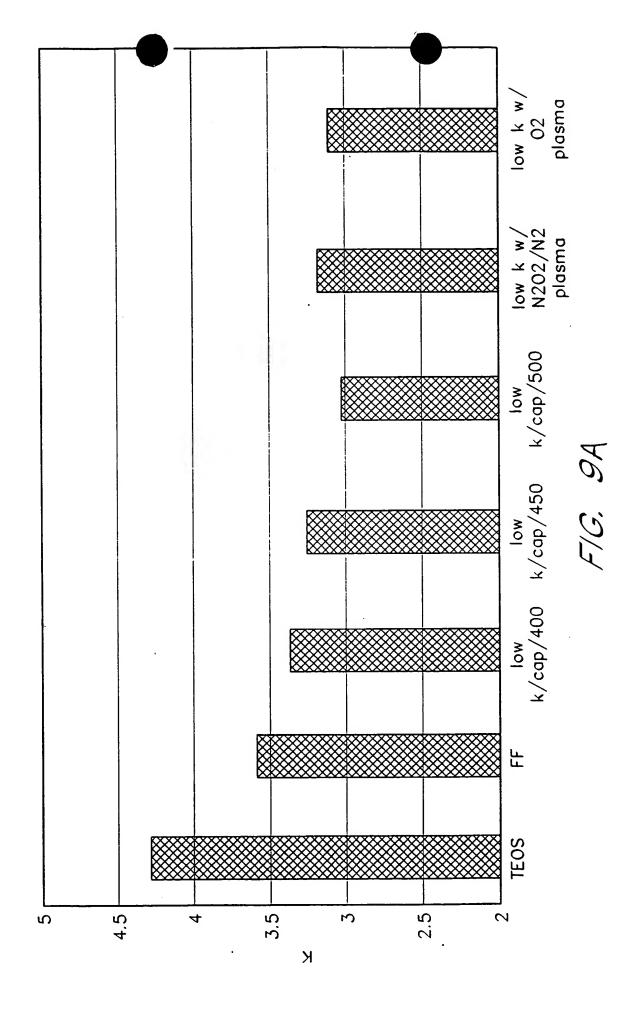
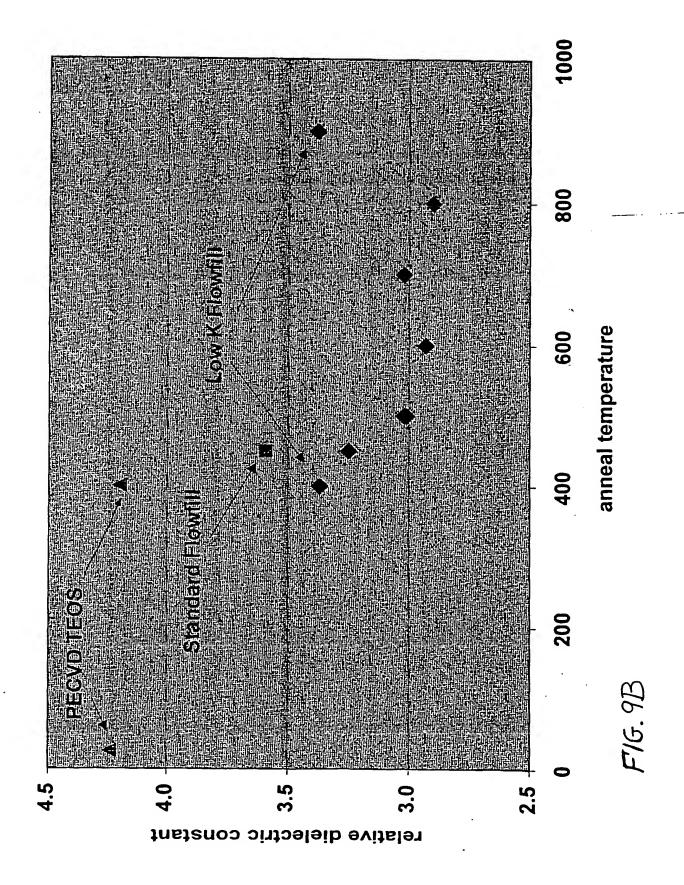
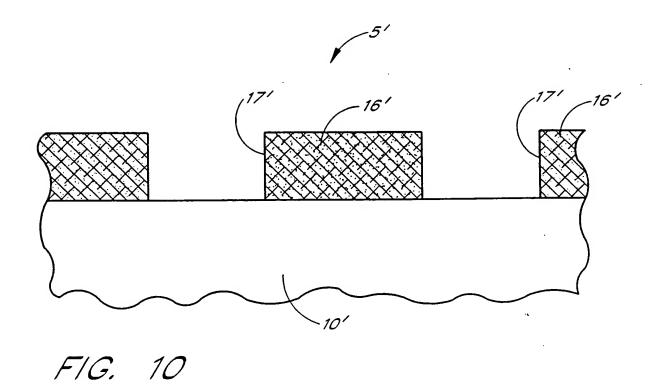


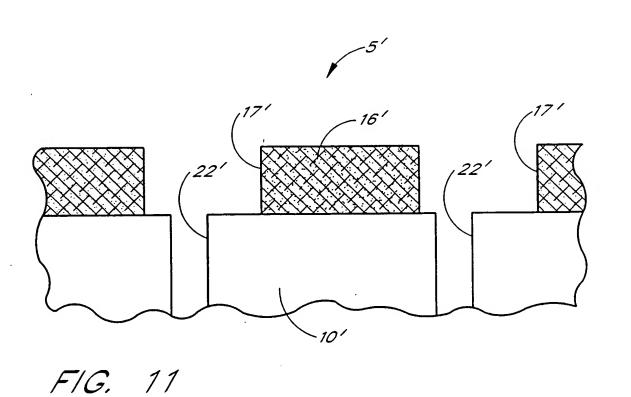
FIG. 6













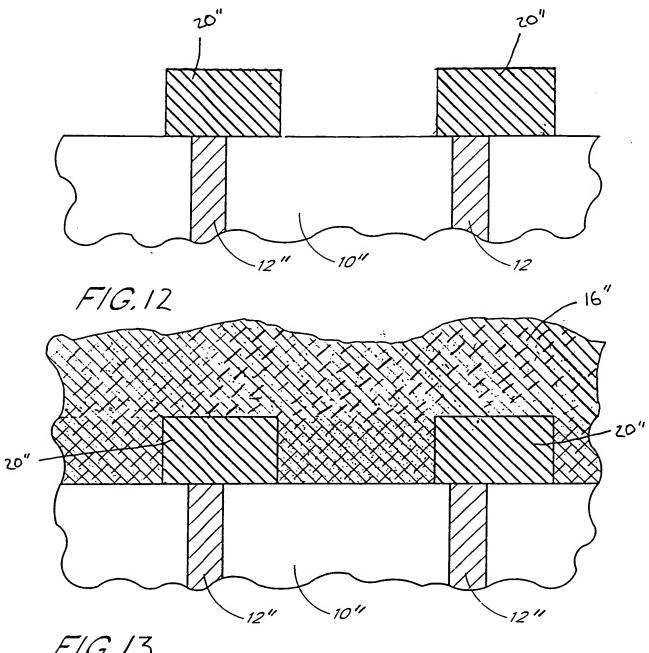
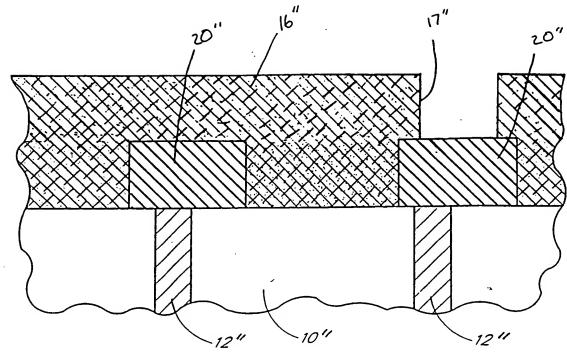
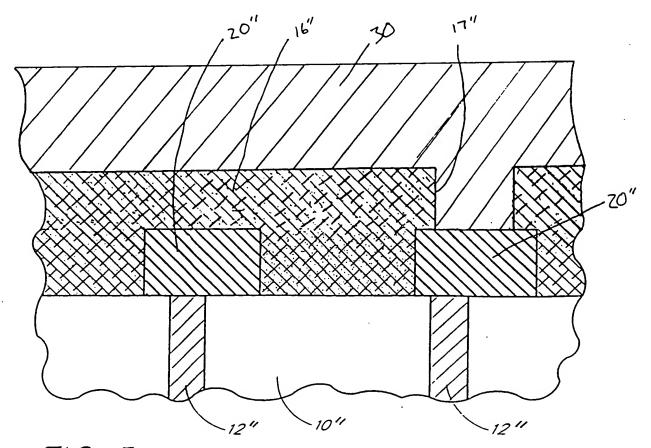


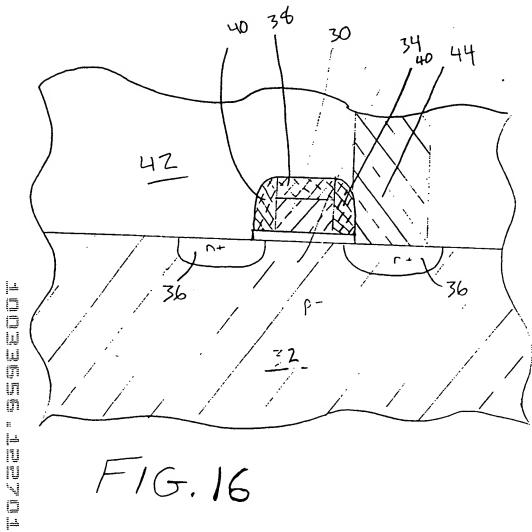
FIG. 13



F1G.14



F/G. 15



F1G.16